

ABSTRACT

A reflective mask blank has a substrate, a multilayer reflective film configured to reflect EUV light, and an absorbing film configured to absorb the EUV light in this order, and has a conductive film on the opposite side of the multilayer reflective film
5 from the substrate. A coefficient of dynamic friction of the conductive film on the surface opposite the substrate is less than 0.45, measured in a nitrogen atmosphere at room temperature.